Chinastandards.org

NATIONAL STANDARD OF THE

PEOPLE'S REPUBLIC OF CHINA

GB/T 14847-2010

Test method for thickness of lightly doped silicon epitaxial layers on heavily doped silicon substrates by infrared reflectance

重掺杂衬底上轻掺杂硅外延层厚度的红外反射测量方法

(English Translation)

Issued on: January 10, 2011 **Implemented on: October 1, 2011**

Issued by: General Administration of Quality Supervision, Inspection and Quarantine of the People's Republic of China;
Standardization Administration of China

Preview: page 1 of 2 shown, full document available. Complete English PDF, instant download:
https://chinastandards.org/standards/gb-t-14847-2010

Chinastandards.org

Table of Contents

Document data

1 Document data

Sector: National standard (Recommended).

Issuing body: General Administration of Quality Supervision, Inspection and Quarantine of the People's Republic of China; Standardization Administration of China.

Date of issue: 2011-01-10.

Date of implementation: 2011-10-01.

Status: obsolete, replaced by GB/T 14847-2025.

Preview: page 2 of 2 shown, full document available. Complete English PDF, instant download:
https://chinastandards.org/standards/gb-t-14847-2010